

Photomask Japan 2022

Best Paper Award Winners



Best Oral Presentation:

Program No.	Presentation Title	Name	Affiliation
9-4 [BACUS]	Verification Methods for Curvilinear and Real-Curve Geometries	Kokoro Kato	Synopsys Japan R&D Center, Japan
10-4	Resist Pattern Resolution on Hard Mask Layer for Photomask	Naoto Yonemaru, Kazuaki Matsui, Itaru Yoshida, Yosuke Kojima, Mitsuharu Yamana	Toppan Photomask Co., Ltd., Japan
12-3	AIMS [®] EUV Phase Metrology: ZEISS solution for the characterization of EUV phase shift masks	Renzo Capelli, Markus Koch, Dmitry Simakov, Klaus Gwosch, Grizelda Kersteen, Tim Helbig	Carl Zeiss SMT GmbH, Germany

Best Poster Presentation:

Program No.	Presentation Title	Name	Affiliation
11-11 [EMLC]	High-precision EUV mask process development	Shingo Yoshikawa, Tsukasa Abe, Yukihiro Fujimura, Masataka Yamaji, Yasutaka Morikawa, Hiroyuki Miyashita, Tatsuya Tomita	Dai Nippon Printing Co., Ltd., Japan